

11-23-01

GP/763

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|---|-------------------------------|-----------------------------|------------------------|
| TRANSMITTAL LETTER<br>(General - Patent Pending)  |                               | Docket No.<br>11675.114     |                        |
| Re Application Of: Kei-Yu Ko  |                               |                             |                        |
| Serial No.<br>08/846,671  | Filing Date<br>April 30, 1997 | Examiner<br>George Goudreau | Group Art Unit<br>1763 |
| Title: UNDOPED SILICON DIOXIDE AS ETCH STOP FOR SELECTIVE ETCH OF DOPED SILICON DIOXIDE |                               |                             |                        |

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Applicant(s): Kei-Yu Ko

Docket No.

11675.114

Serial No.  
08/842,671Filing Date  
April 30, 1997Examiner  
George GoudreauGroup Art Unit  
1763

Invention: DOPED SILICON DIOXIDE AS ETCH STOP FOR SELECTIVE ETCH OF DOPED SILICON DIOXIDE

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